

DERWENT- 2000-215410

ACC-NO:

DERWENT- 200019

WEEK:

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TITLE: Preparation of sublimable adamantanols, useful as materials for semiconductive resists by reaction of sublimable adamantanols, distillation of resultant molten adamantanol derivatives, and conversion of the derivatives to sublimable adamantanols

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PRIORITY-DATA: 1998JP-206068 (July 22, 1998)

PATENT-FAMILY:

PUB-NO	PUB-DATE	LANGUAGE
JP 2000038362 A	February 8, 2000	JA

APPLICATION-DATA:

PUB-NO	APPL-DESCRIPTOR	APPL-NO	APPL-DATE
JP2000038362A	N/A	1998JP-206068	July 22, 1998

INT-CL-
CURRENT:

TYPE	IPC	DATE
CIPP	<u>C07 C 27/02</u>	20060101
CIPS	<u>C07 C 29/80</u>	20060101
CIPS	<u>C07 C 35/37</u>	20060101
CIPS	<u>C07 C 67/03</u>	20060101
CIPS	<u>C07 C 67/08</u>	20060101
CIPS	<u>C07 C 67/14</u>	20060101
CIPS	<u>C07 C 69/54</u>	20060101

ABSTRACTED-PUB-NO: JP 2000038362 A

BASIC-ABSTRACT:

NOVELTY - Highly pure sublimable adamantanols are prepared by reaction of sublimable adamantanols or their alkoxides, distillation of the resultant molten adamantanol derivatives, and conversion of the resultant distilled molten adamantanol derivatives to the sublimable adamantanols.

DETAILED DESCRIPTION - Highly pure sublimable adamantanols of formula (I) are prepared by reaction of sublimable adamantanols or their alkoxides, distillation of the resultant molten adamantanol derivatives of formula (II), and conversion of the resultant distilled molten adamantanol derivatives to the sublimable adamantanols. R1, R2 = H, hydroxy, 1-6C alkyl (one is hydroxy and the other is H or 1-6C alkyl); R3 = H, 1-6C alkyl; R4, R5 = H, 1-6C alkyl, lower alkoxylcarbonyloxy, lower alkyloxymethoxy, etc. (one is lower alkylcarbonyloxy, lower alkyloxymethoxy, etc. and the other is H or 1-6C alkyl); R6 = H, 1-6C alkyl.

USE - The product compounds are useful starting materials in manufacturing semiconductive resists.

ADVANTAGE - The preparation readily and effectively affords the products of high purity.

TITLE- PREPARATION SUBLIMATION USEFUL MATERIAL SEMICONDUCTOR RESIST
TERMS: REACT DISTIL RESULT MOLTEN DERIVATIVE CONVERT

DERWENT-CLASS: E15 L03

CPI-CODES: E09-C01; L04-C05;

CHEMICAL- Chemical Indexing M3 *01* Fragmentation Code G031 G038
CODES: G060 G740 H4 H401 H461 H8 M210 M211 M212 M213 M214 M215
M216 M231 M232 M233 M240 M280 M281 M282 M320 M415 M510
M520 M530 M541 M720 N104 N163 N164 N241 N242 N362 N513
Q431 Q454 Ring Index Numbers 03624 Markush Compounds
0019CH101

SECONDARY-ACC-NO:

CPI Secondary Accession Numbers: 2000-065736